

In re Application of:
Lawrence C. Lei

Confirmation No.: 4370

For: Apparatus and Method for Vaporizing Solid Precursor for CVD or Atomic Layer Deposition

Group Art Unit: 3742

Examiner: Sang Y. Paik

**Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450**

Dear Sir:

RESPONSE TO FINAL OFFICE ACTION DATED OCTOBER 13, 2006

In response to the Final Office Action dated October 13, 2006, having a shortened statutory period for response set to expire on January 13, 2007, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/APPM/005191.C1(Y1)/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper. **Remarks** begin on page 5 of this paper.